



WAM

deutsche  
nanoschicht

chemistry meets energy

# All-Chemical-Solution Coated Conductors at Deutsche Nanoschicht GmbH

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Federal Ministry  
of Economics  
and Technology

## Outline

- Deutsche Nanoschicht GmbH
- Process technology
- Expanded pilot line
- Performance
- Technical HTS conductor
- Summary



## Deutsche Nanoschicht GmbH

- Since June 2013 part of BASF group
- 63 employees , located in Rheinbach and Heidelberg, Germany
  - High Temperature Superconducting (HTS) wires,
    - chemical solution deposition, ceramic functional layers, ink-jet-printing, epitaxial growth
  - Additive manufacturing / 3D-printing



## High Temperature Superconductors

- Challenges for development and production
  - Best price performance ratio (€/kAm)
  - Scalable large volume production
  - Reliable and in-time supply
  - Flexible but mechanically and electrically stable



## Process Technology

- Chemical solution deposition
  - Chemical solution deposition (CSD) for all layers is considered to be the „most promising and most challenging process“
  - Unique and protected CSD-multi-layer technology



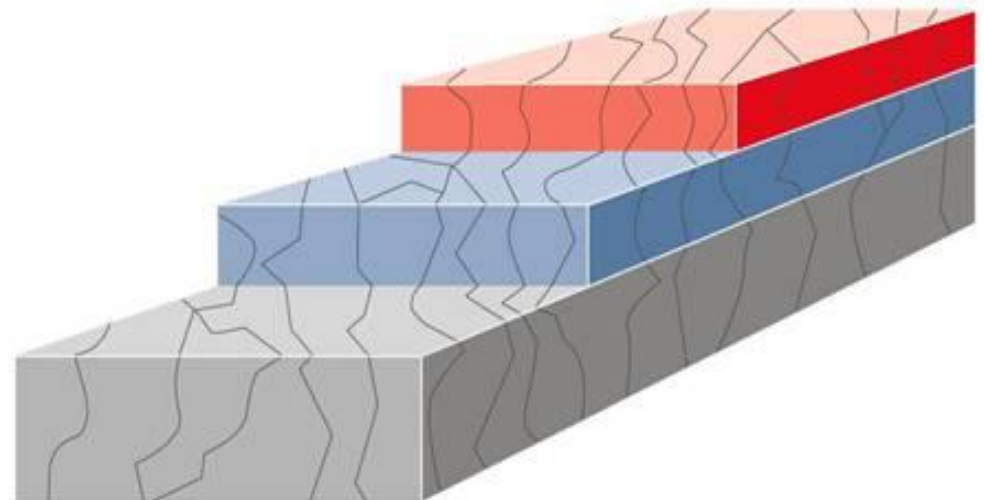
## Process Technology

- HTS wire architecture – thin flexible ceramic coatings

**Superconductor layer**  
 **$\text{YBa}_2\text{Cu}_3\text{O}_x$  (YBCO)**

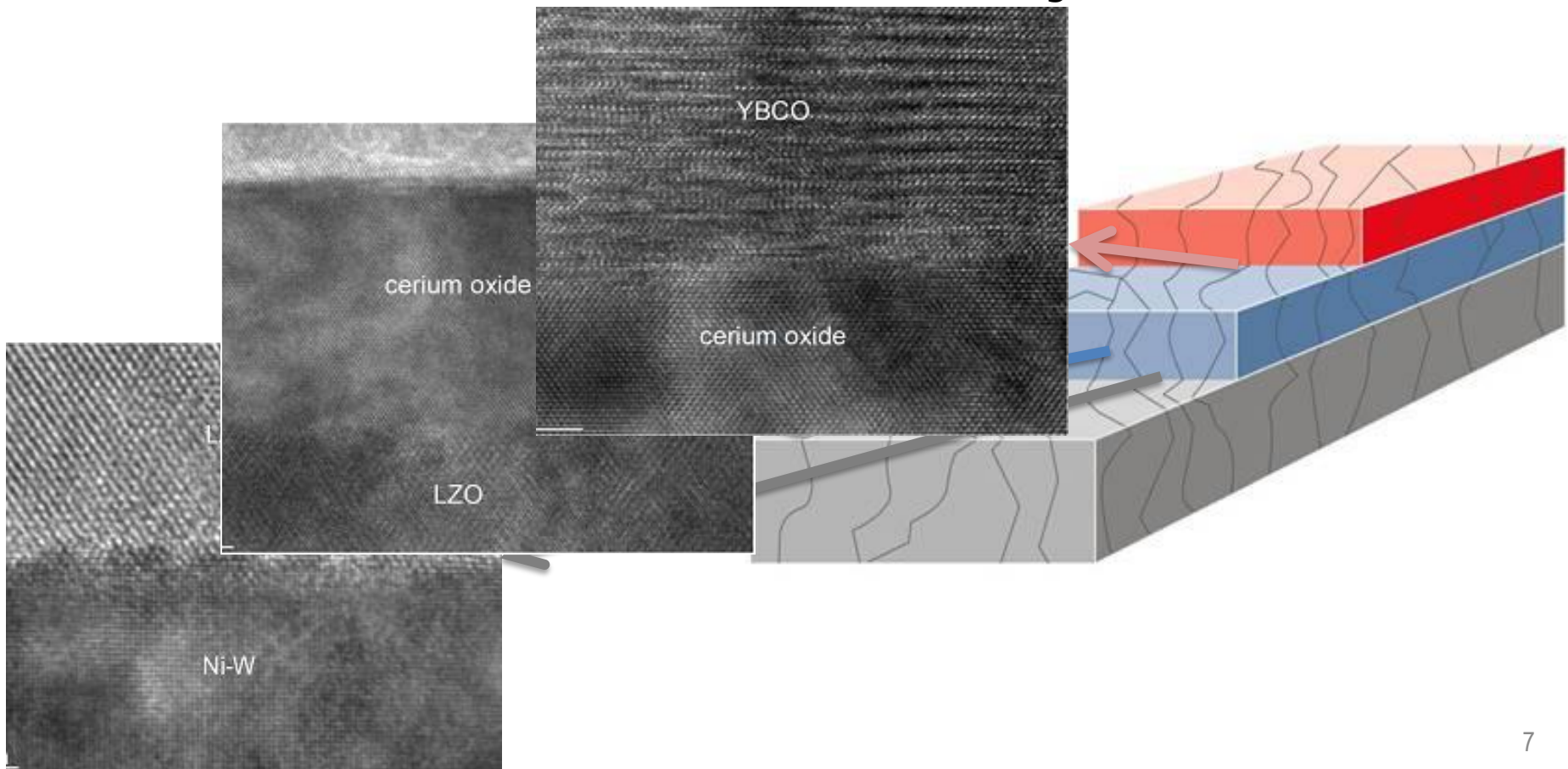
**Buffer layer**  
 **$\text{La}_2\text{Zr}_2\text{O}_7$  (LZO),  $\text{CeO}_2$**

**Metal alloy substrate**  
**NiW-alloy**



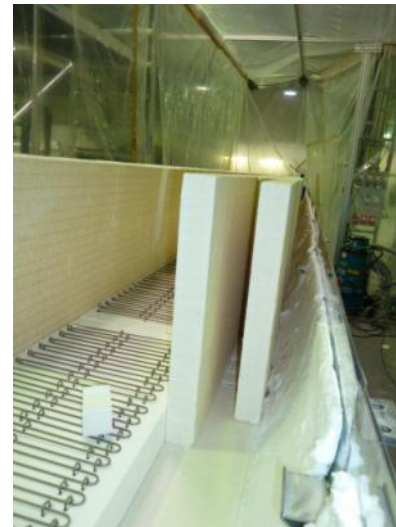
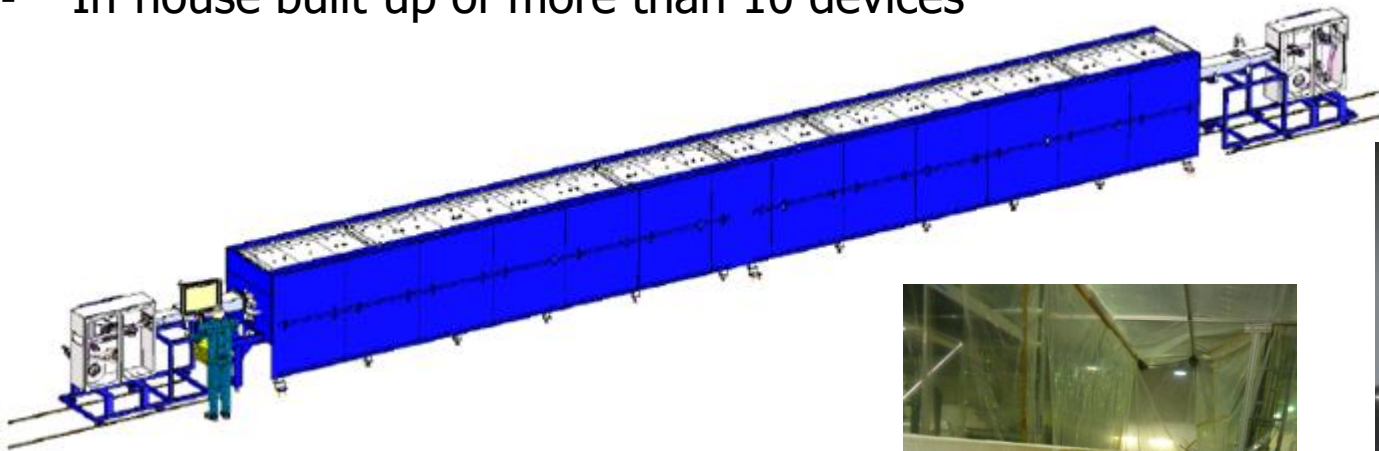
## Process Technology

- HTS wire architecture – thin flexible ceramic coatings



## Expanded pilot line

- Construction of key process devices in house
- In-house built-up of more than 10 devices





## Expanded pilot line

- Opening of expanded pilot line in Rheinbach at 10<sup>th</sup> May 2016



## Expanded pilot line

- EPL construction until mid 2016 completed
- EPL capacity ramp-up completed. Increasing the yield is ongoing.
- Theoretical capacity > 200km technical HTS wire
- Started sampling for projects in 2016



Lab processing

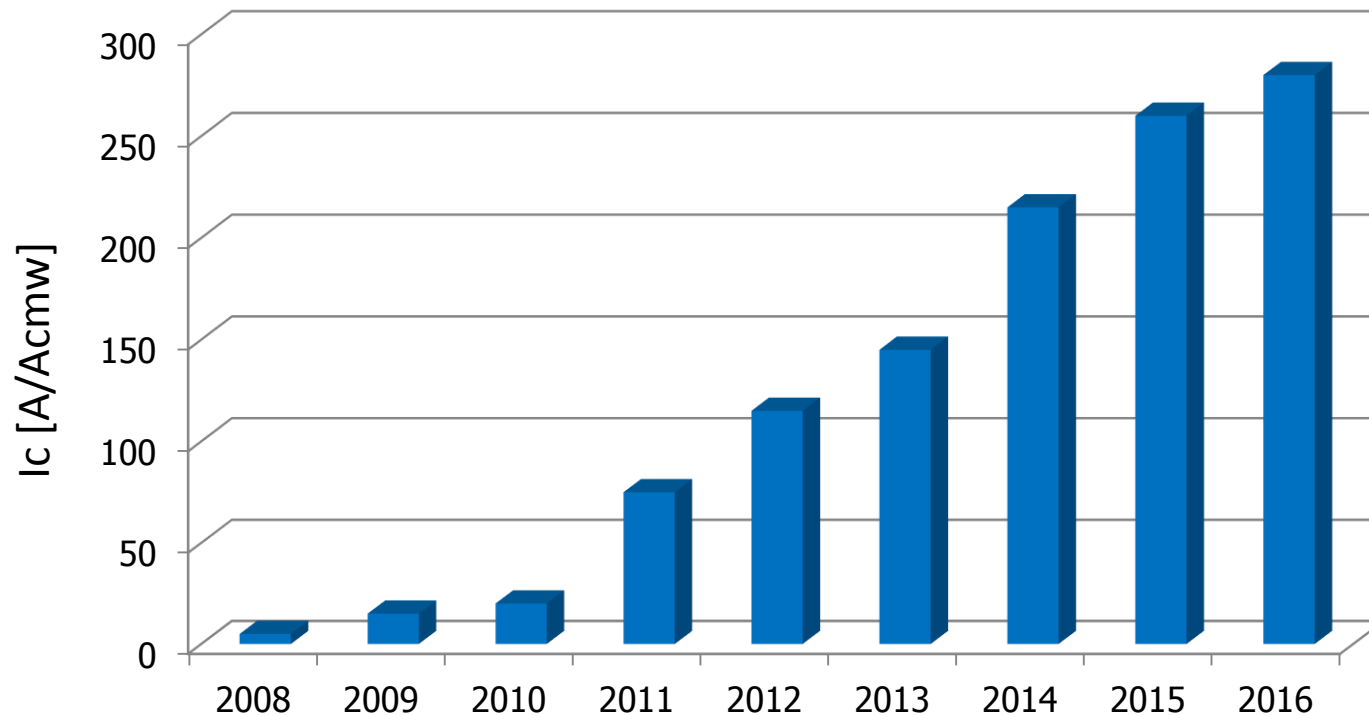


Expanded Pilot Line

## Performance

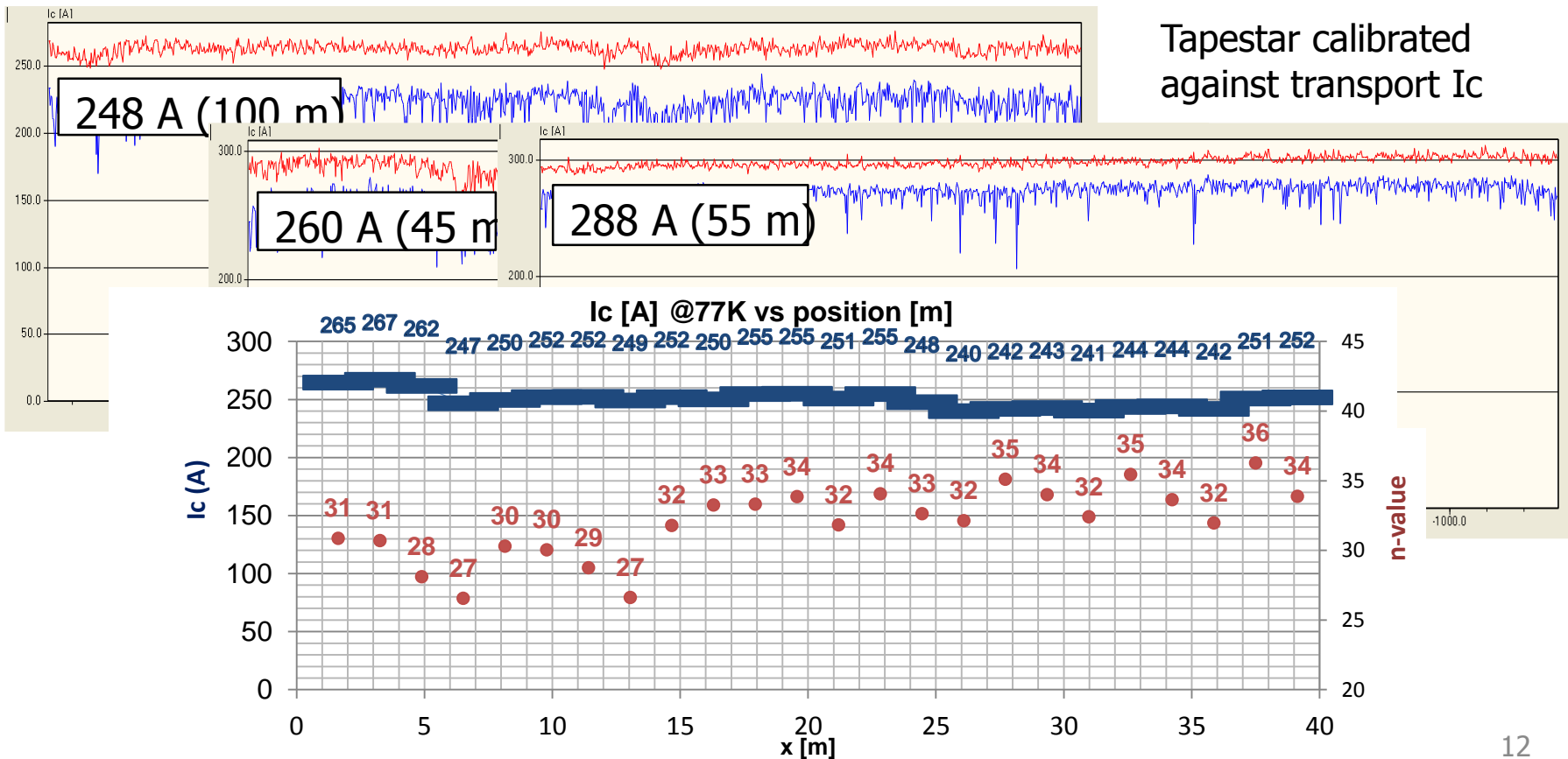
- Development with industrial partners over nearly 10 years
  - Long lengths samples >20m

VDM Metals  
Honeywell  
Heraeus



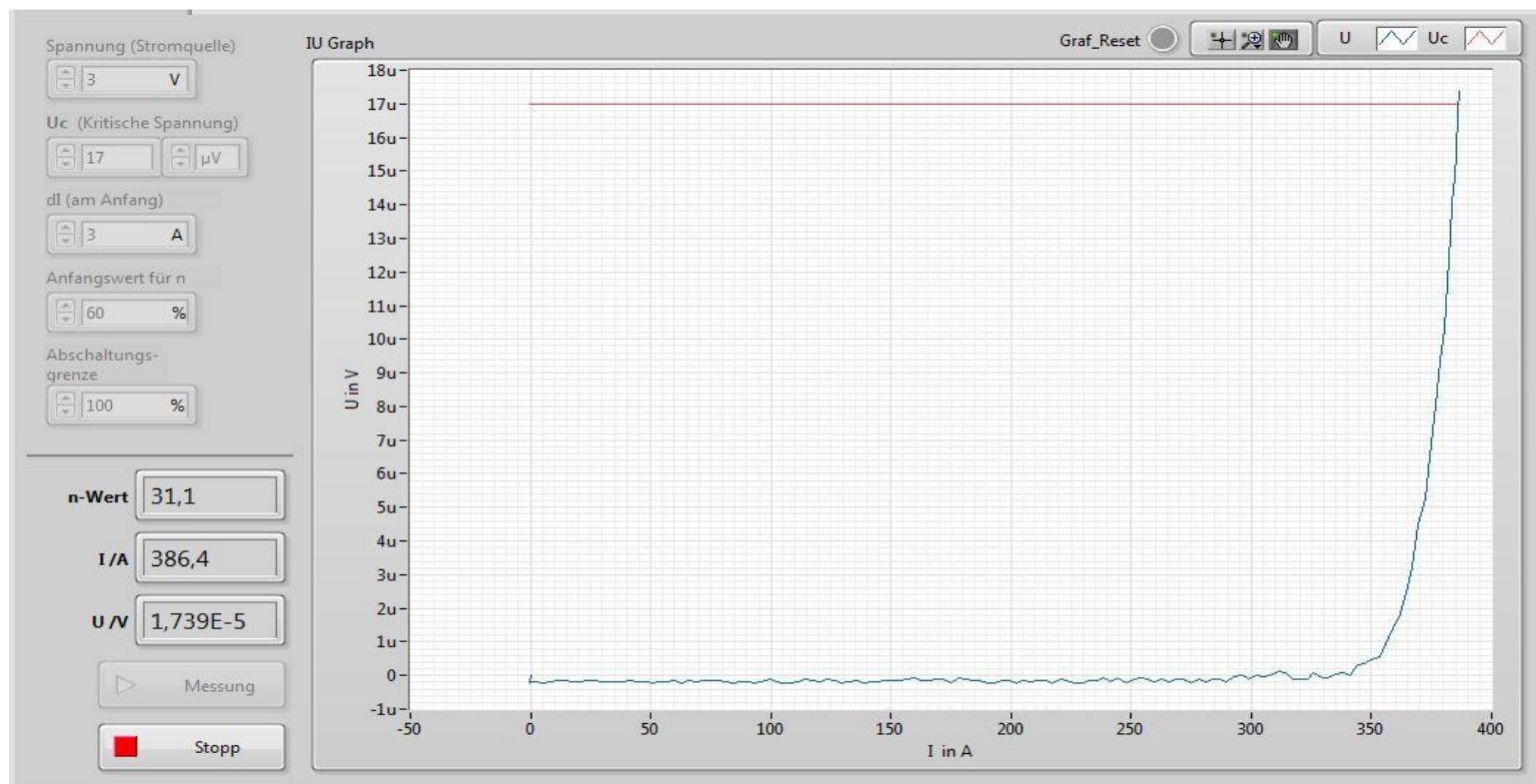
## Performance

- D-nano has produced in 2016 1cm wide 50-100m tapes with  $I_c \cong 250$  A/cm



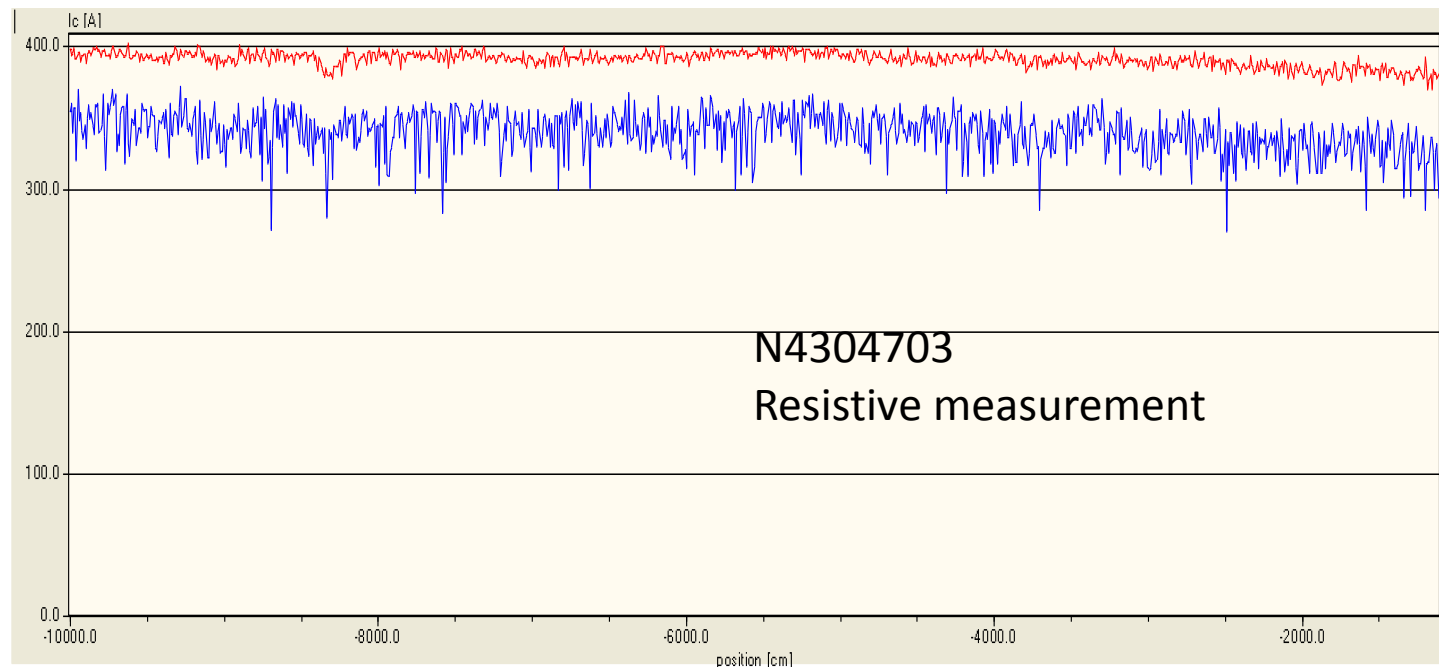
## Performance

- Recent record value on EPL with length >20m (10mm width uncut)



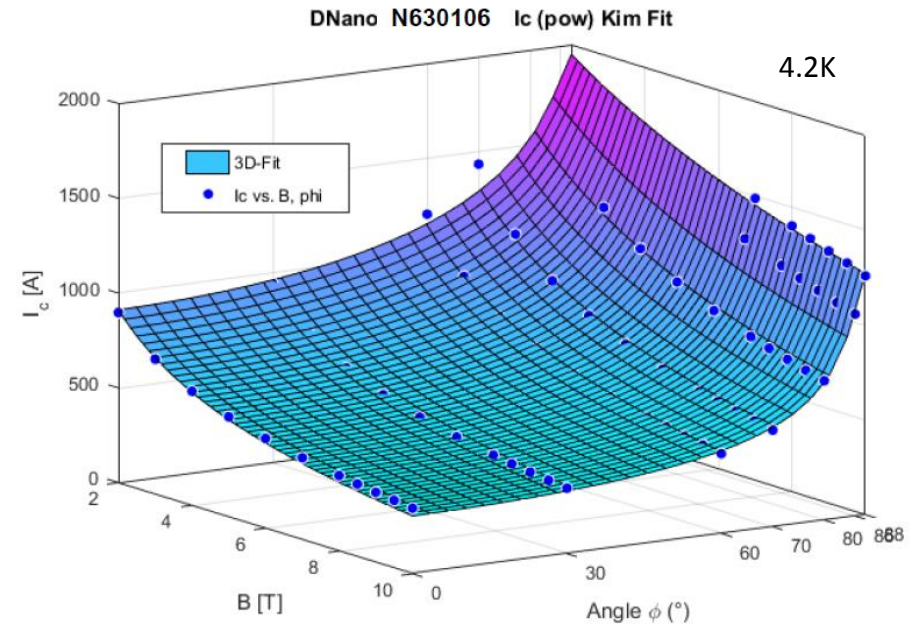
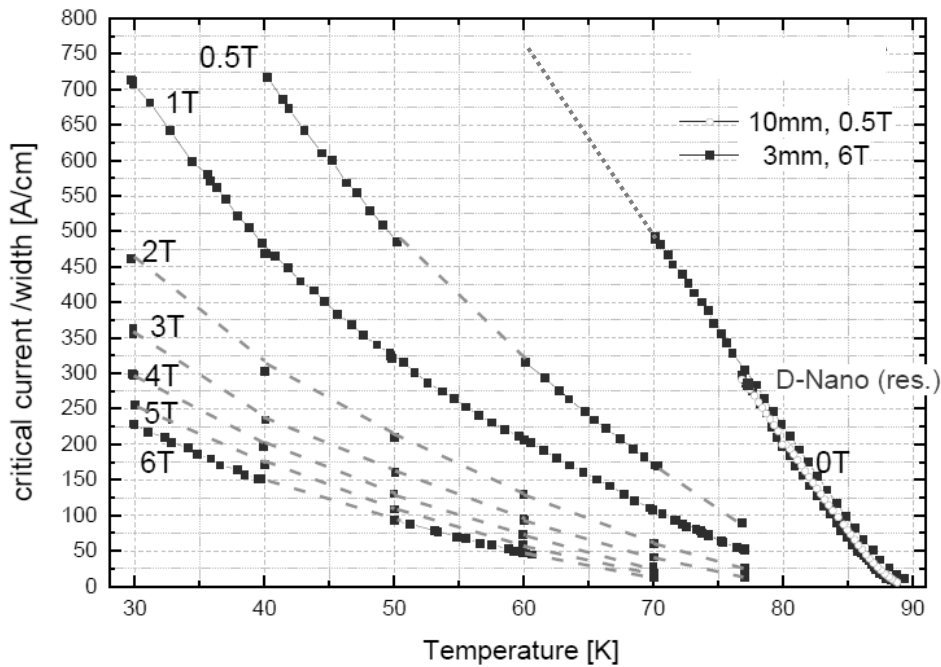
## Performance

- EPL at 6 month after opening: 90 m long / 10 width uncut



## Performance

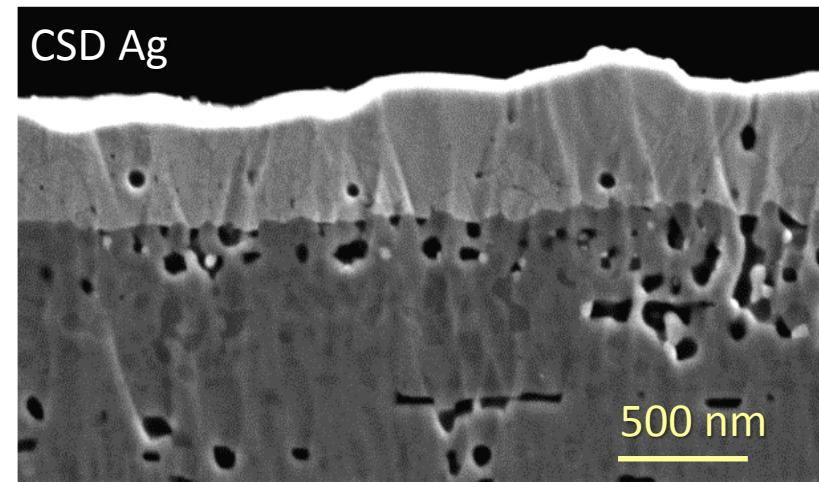
- Typical behavior in magnetic fields



## Technical HTS conductor

- Silver coating
  - Unique chemical solution deposition process
  - Fast and vacuum-free processing
  - Thin and dense coating

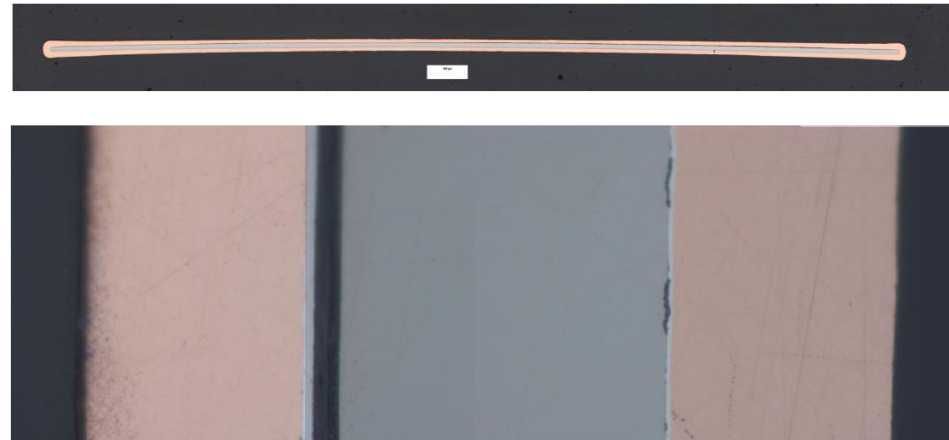
| Sample  | $T_c$<br>(K) | $\rho_{\text{contact}}$<br>( $\mu\Omega\text{cm}^2$ ) |
|---------|--------------|---|
| N433460 | 90.1         | < 0.45  |
| N432135 | 88.2         | < 0.68  |
| N432161 | 88.2         | < 0.38  |
| N432162 | 86.4         | < 0.45  |
| N433507 | 89.9         | < 0.60  |
| N433508 | 89.4         | < 0.35  |
| N433509 | 89.3         | < 0.30  |





## Technical HTS conductor

- Copper electro-plating
  - Homogeneous coating
  - Variable copper layer thickness
  - Low contact resistance

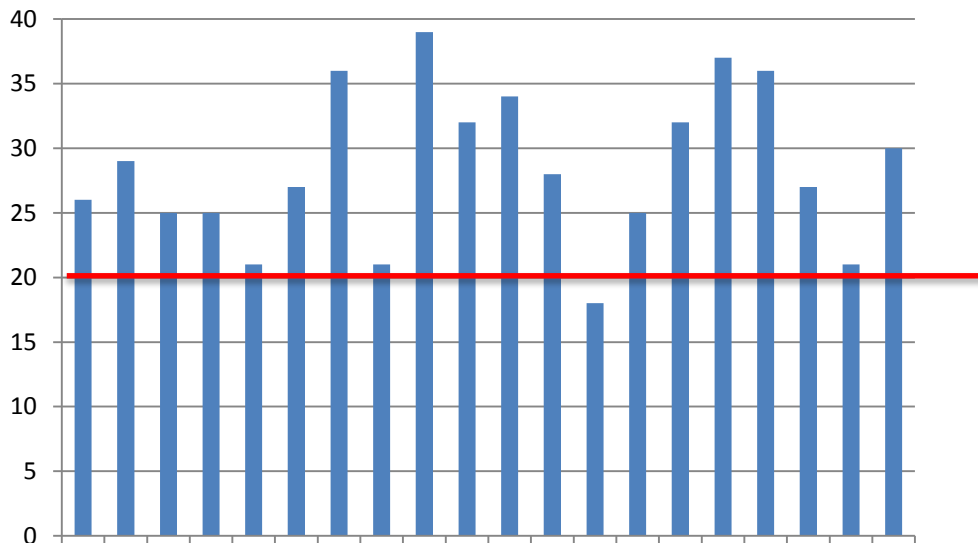


Cu-plated HTS conductor,  
45 $\mu$ m single Cu-layer

| Sample   | Cu layer thickness | $T_c$ (K) | $\rho_{\text{contact}}$ ( $\mu\Omega\text{cm}^2$ ) |
|----------|--------------------|-----------|--|
| N630078  | 9 $\mu$ m          | 89.8      | 7.5  |
| N630095  | 40 $\mu$ m         | 89.8      | 3.7  |
| N630102  | 9 $\mu$ m          | 89.8      | 2.3  |
| N630106Z | 45 $\mu$ m         | 88.7      | 4.2  |

## Technical HTS conductor

- Delamination strength
  - c-axis tensile av. 28(6) MPa (bare insert, non-laminated)
  - Architecture suitable for most energy applications



Threshold for  
cable applications

Specimen geometry: 12.8 x 6.4 mm<sup>2</sup>  
(soldered on 10 x 20 mm<sup>2</sup> sample)

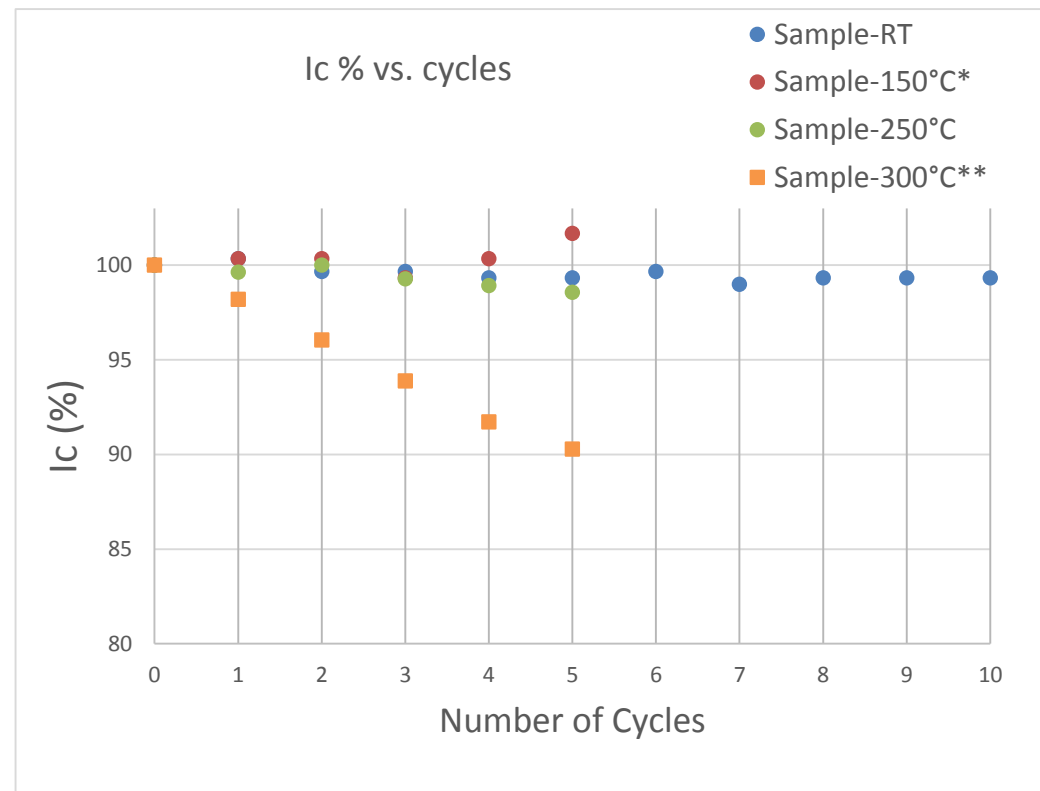
## Technical HTS conductor

### Temperature Stability

Tested CC with copper coating

- 250 deg C for >1 hour
- 300 deg C for 30 min

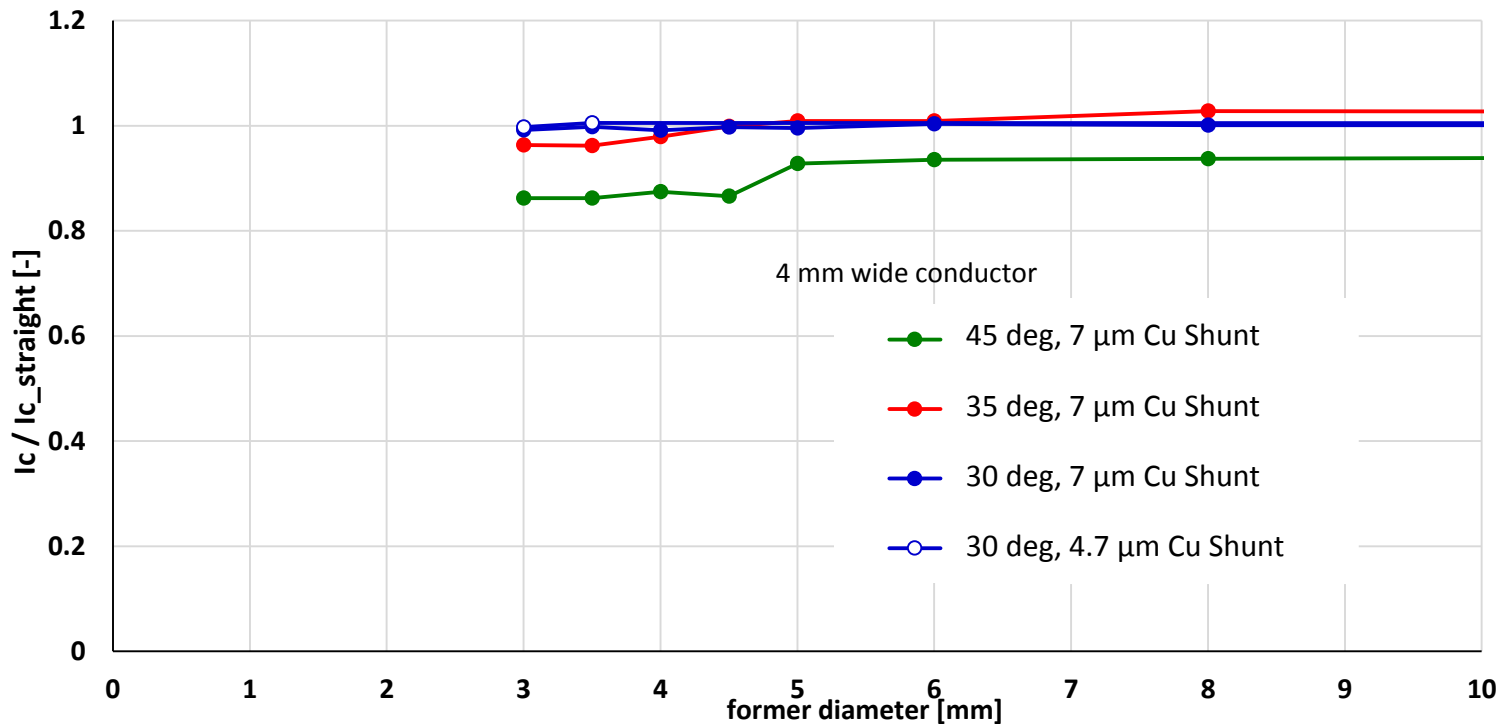
Material suitable for welding or soldering



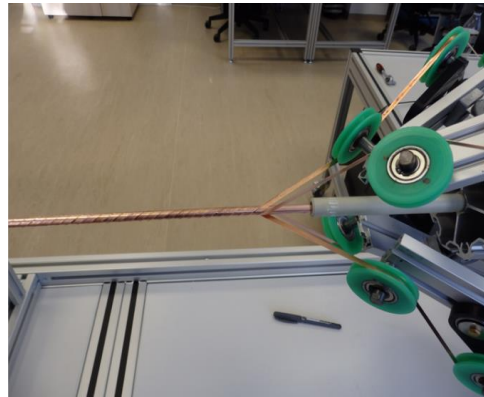
Duration per cycle : 30 minutes @ peak T

## Technical HTS conductor

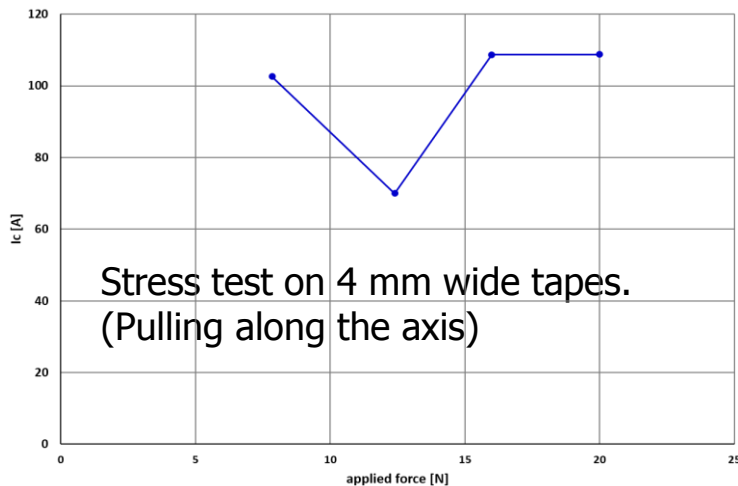
Bending tests ( e.g. for CORT geometry )



## CORT Cable



- about 9 m long
- 2 layers
- 4 tapes in each layer
- lay angle about  $33^\circ$
- tension during winding 20 N

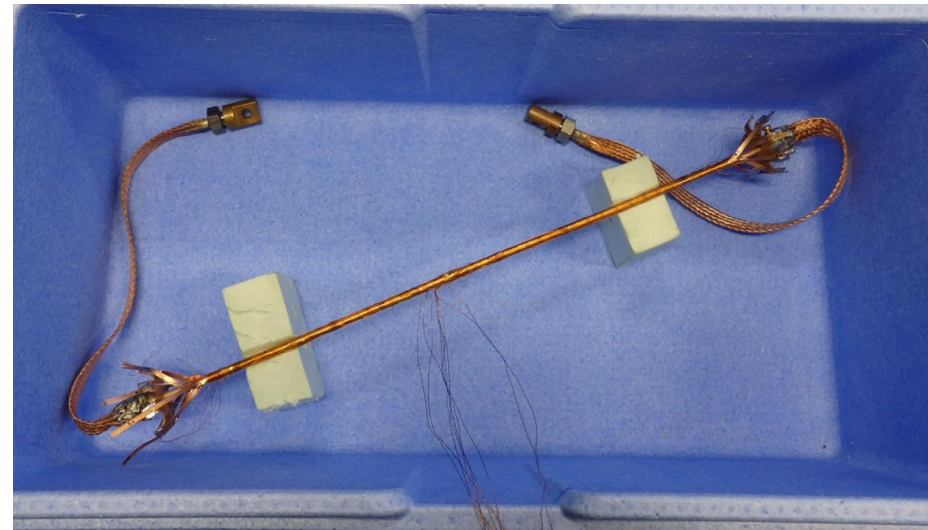


## Technical HTS conductor

CORT cable, IEE Bratislava:

- 4mm copper coated tape
- 2 layers, 4 filaments each
- 6.35 mm tube
- 32° lay angle

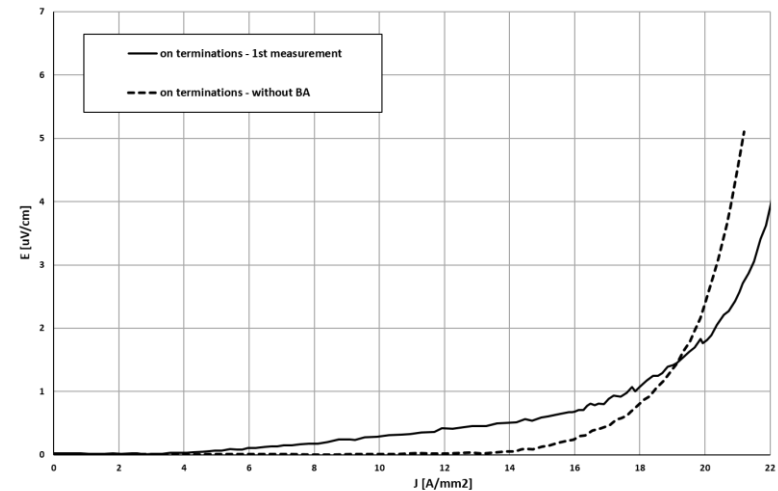
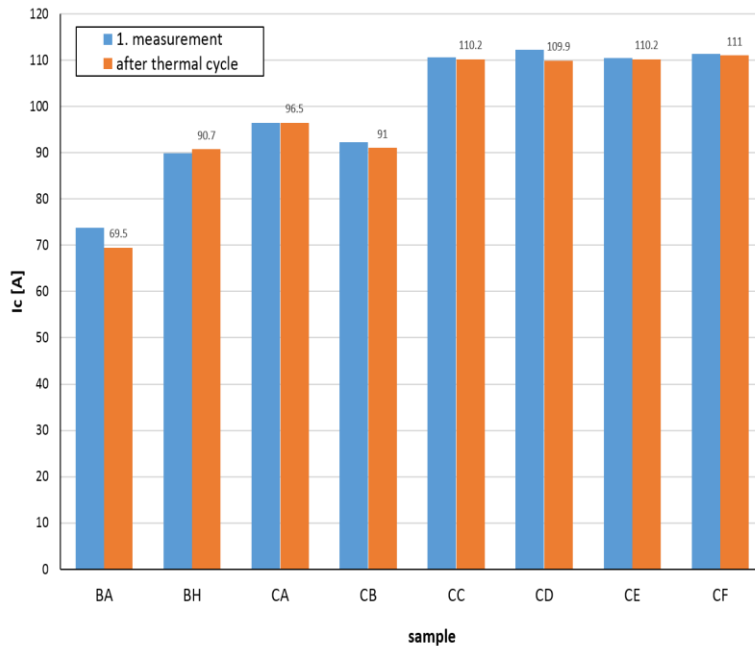
eurotapes



# CORT cable



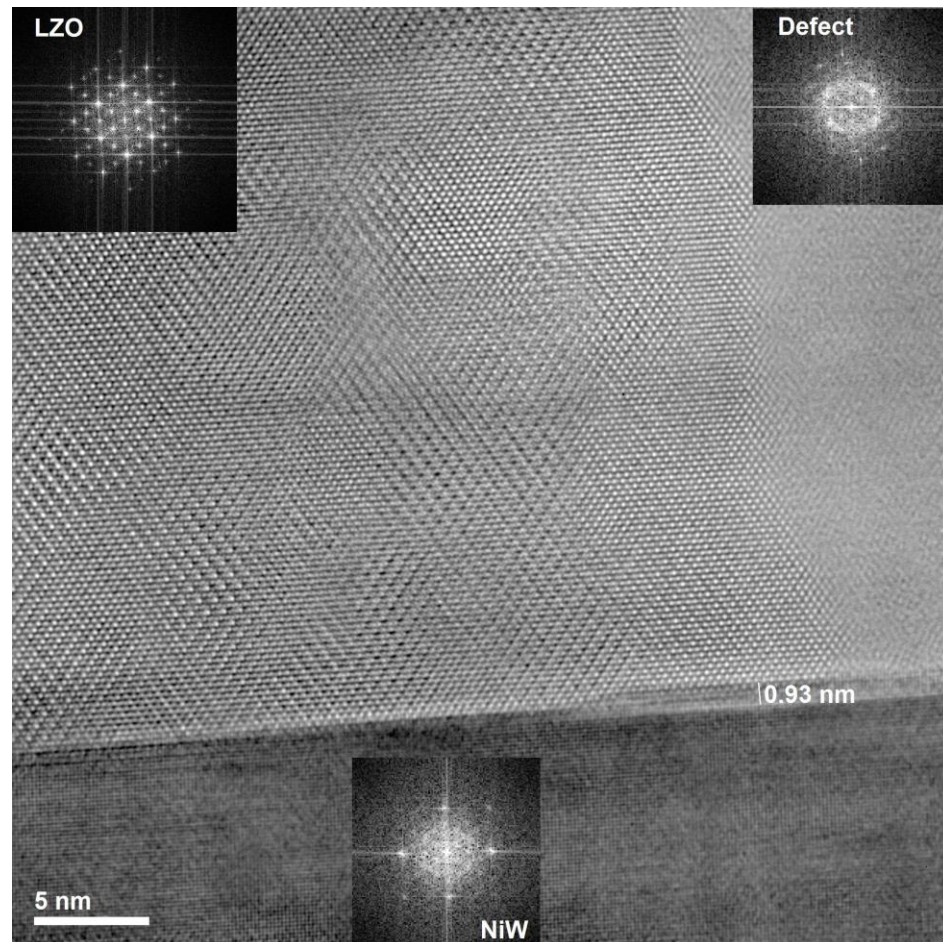
8 individual 4 mm filaments in 2 layers



Total current in the CORT: >600 A  
 Technical current density: 18 A/cm<sup>2</sup>

## Process challenges

- Process stabilization
- Large area processing
- High throughput
- Local dropouts
  - Interface defects
  - Handling
  - Raw materials
- customization



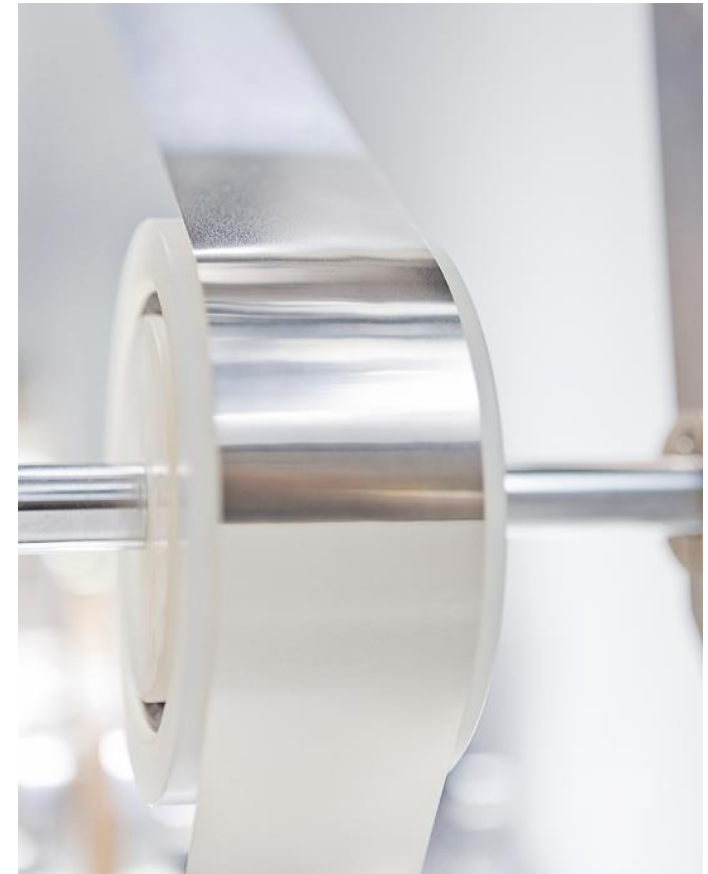
Interface defect: loss of orientation



## Summary

- Chemical solution deposition enables economic mass production of high temperature superconducting tapes
- Deutsche Nanoschicht reached significant performance increase over last years and starts pilot production in 2016/17
- HTS conductor successfully customized for applications
- First samples provided to customers

... but challenges remain in product and process development





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**Thanks for your attention**

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